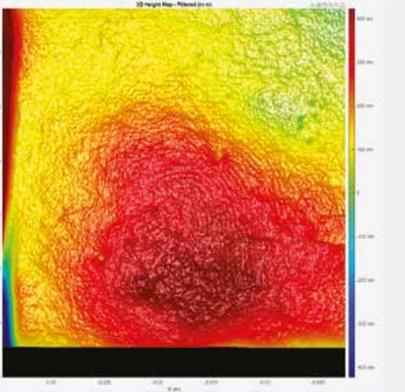
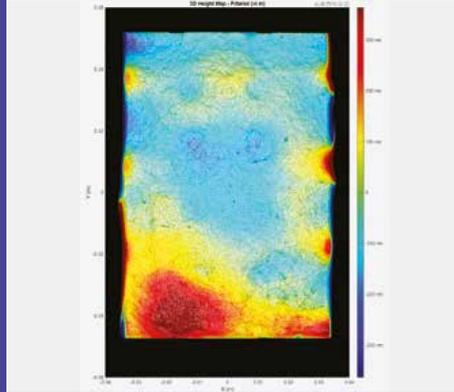


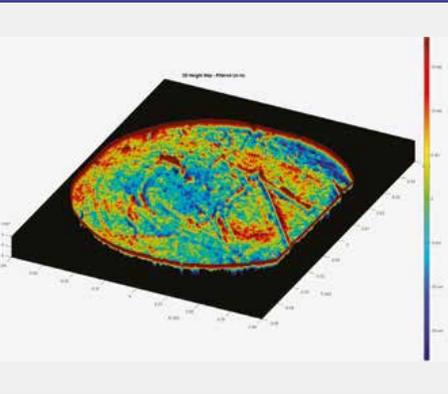
D-SURFACE TESTING SAMPLES



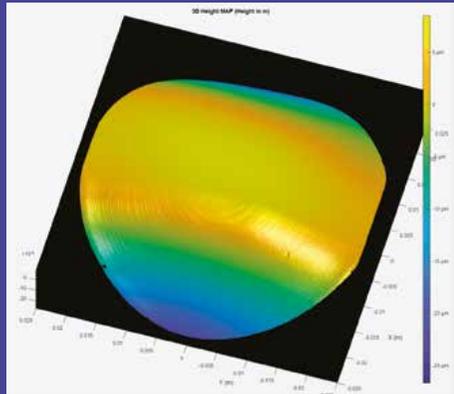
Phone fingerprint



Phone screen



Wafer roughness



Wafer shape

SURFACE

Deflectometry-based
Surface Inspection &
Flatness measurement

Local and Global inspection nm to mm
One shot measurement
Down to nanometer scale



measurement
that goes beyond limits

CONTACT

sales@dip-view.com
Toulouse • France

DS-EH-01-D-Surface View ©april2023



measurement
that goes beyond limits



FEATURES

Vertical dynamic range
1 nm to 1mm

Field of view
up to 300mm

Lateral resolution
down to 10µm

Full diameter measurement of the sample without stitching
1 shot measurement

Software
Easy-to-use software interface

APPLICATIONS

Texture
2D and 3D roughness and waviness

Form
2D and 3D bow and shape

Stress
2D and 3D thin film stress

Defect review
2D and 3D defect surface topography

INDUSTRIES

Universities, research labs, and institutes

Semiconductor and compound semiconductor

Solar

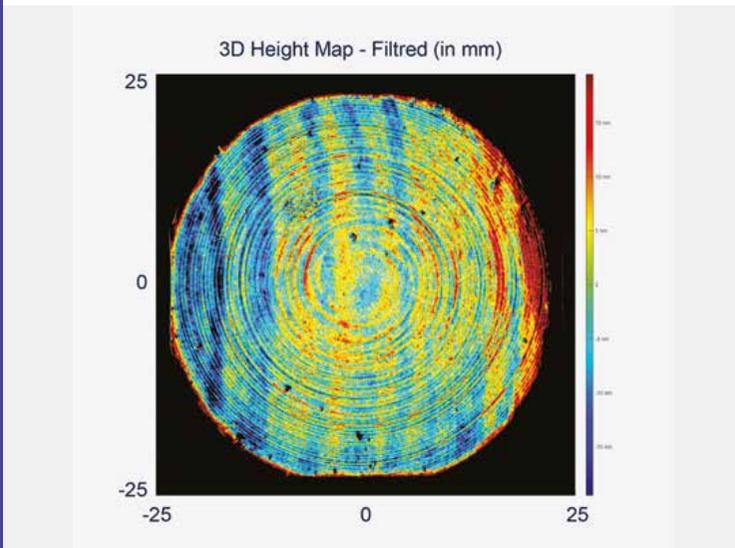
LED Manufacturing

Data storage
Automotive
Medical devices

D-Surface View is intended to help manufacturers of wafers up to 300-mm diameter reduce costs and chipmakers to improve yields for devices made with finest process technology.

The equipment can be used for wafer surface quality control, it qualifies surface roughness, shape, flatness and topography in one single measurement of a bare or processed wafer.

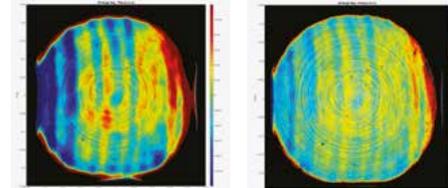
Its very high resolution performances bring fast, reliable and highly sensitive solution particularly adapted to off-line or in-line, surface local / global inspections in multiple industries.



OFFLINE ANALYSIS SOFTWARE

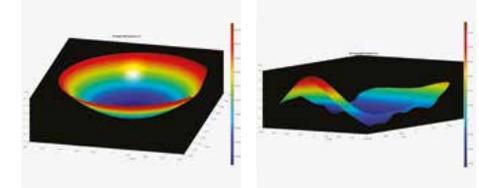
- > 2D and 3D step heights with cursors and histogram analysis
- > 2D profiles and 3D views of the measurements
- > 2D and 3D roughness and waviness analysis
- > 2D and 3D filtering and leveling techniques
- > Thin film stress and sample bow calculation

MEASUREMENT APPLICATIONS



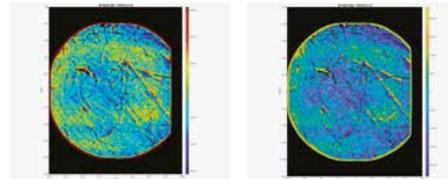
Texture: Roughness and Waviness

Measure 2D and 3D texture while quantifying the sample's roughness and waviness. Distinguish between roughness and waviness components using software filters.



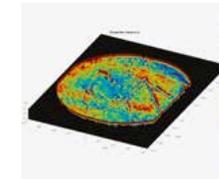
Form: Bow and Shape

Measure the 2D shape or bow of a surface. Quantify the height and radius of curved structures, such as a lens.



Defect Analysis

Measure the topography of defects, such as the depth of a scratch.



Thin Film Stress

Measure 2D stress induced during the manufacture of semiconductor or compound semiconductor devices having multiple process layers.

TECHNICAL CHARACTERISTICS

	D-Surface View 100	D-Surface View 200	D-Surface View 300
Measuring surface	100 × 100 mm ² (flat object)	200 × 200 mm ² (flat object)	300 × 300 mm ² (flat object)
Out of plane tolerance	+/- 1mm	+/- 2mm	+/- 3-4mm
Lateral resolution	22 µm	44 µm	66 µm
Vertical resolution	<1 nm	1-2 nm	2 nm
Measurement time	typ. 1 sec	typ. 1 sec	typ. 1 sec
Repeatability	<0,05 nm rms	<0,05 nm rms	<0,05 nm rms
Cameras	20 MPixels	20 MPixels	20 MPixels
Outer dimensions W × H × D	400 × 300 × 300 mm ³	450 × 600 × 400 mm ³	500 × 900 × 500 mm ³